

Supplementary Materials for Room temperature multiplexed gas sensing using chemical-sensitive 3.5-nm-thin silicon transistors

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Supplementary Materials

S1. Sensor characteristics of an unfunctionalized CS-FET sensor

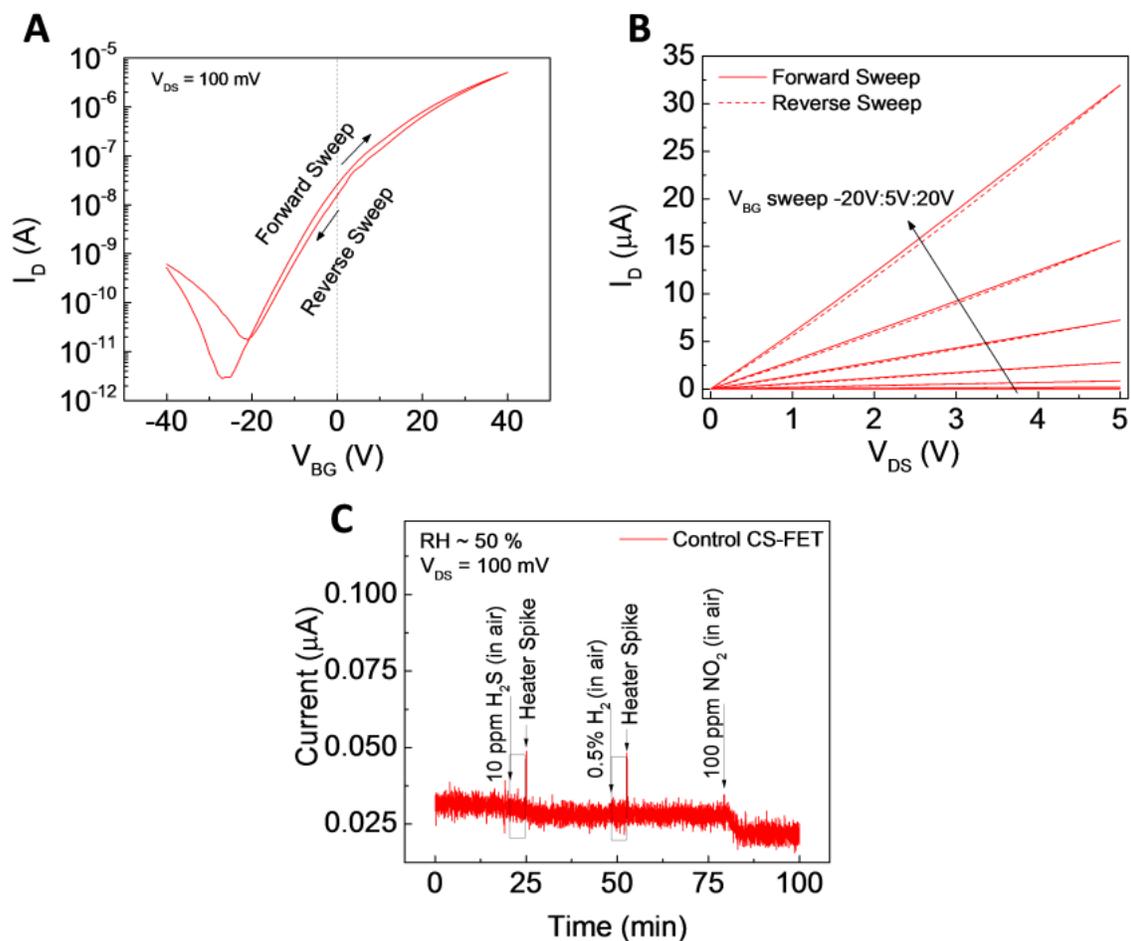


fig. S1. Properties of a control CS-FET without any sensing film. (A) Double sweep electrical transfer curve (I_D - V_{BG}), (B) double sweep electrical output curve (I_D - V_{DS}) and (C) sensor response test to 10 ppm H_2S , 0.5% H_2 and 100 ppm NO_2 in air.

S2. Nanoparticle sensing layer sparsity analysis

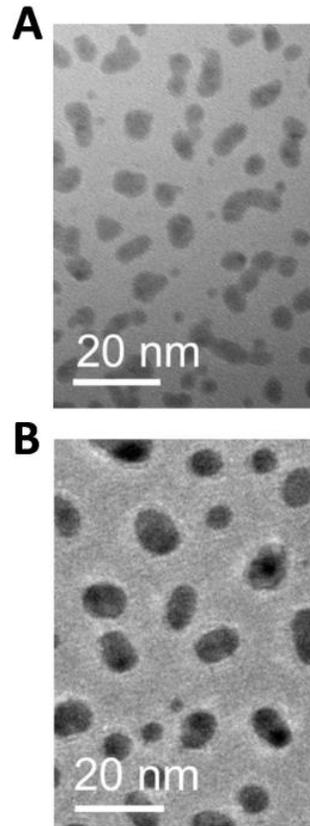


fig. S2. Top-down TEM image of an ultrathin Pd_{0.3nm}Au_{1nm} on Si₃N₄ grids. (A) as-deposited and (B) air-annealed at 250°C for 1 minute.

S3. Effect of silicon channel thickness on CS-FET sensitivity

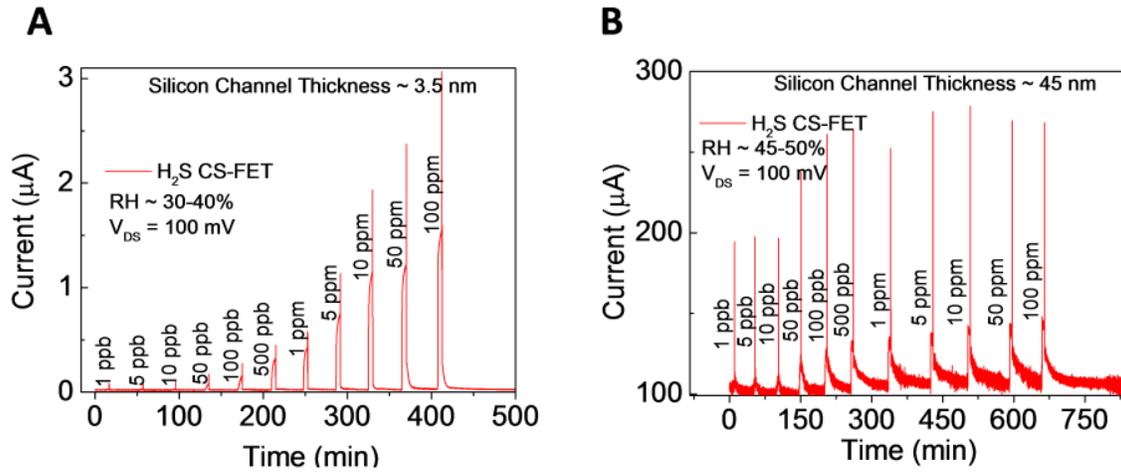


fig. S3. CS-FET sensor response dependence on silicon channel thickness. (A) High sensitivity from 3.5 nm thin silicon channel and **(B)** low sensitivity from 45 nm thick silicon channel Pd-Au CS-FET (H₂S sensor).

S4. CS-FET sensor response to temperature, relative humidity, and room temperature recovery characteristics

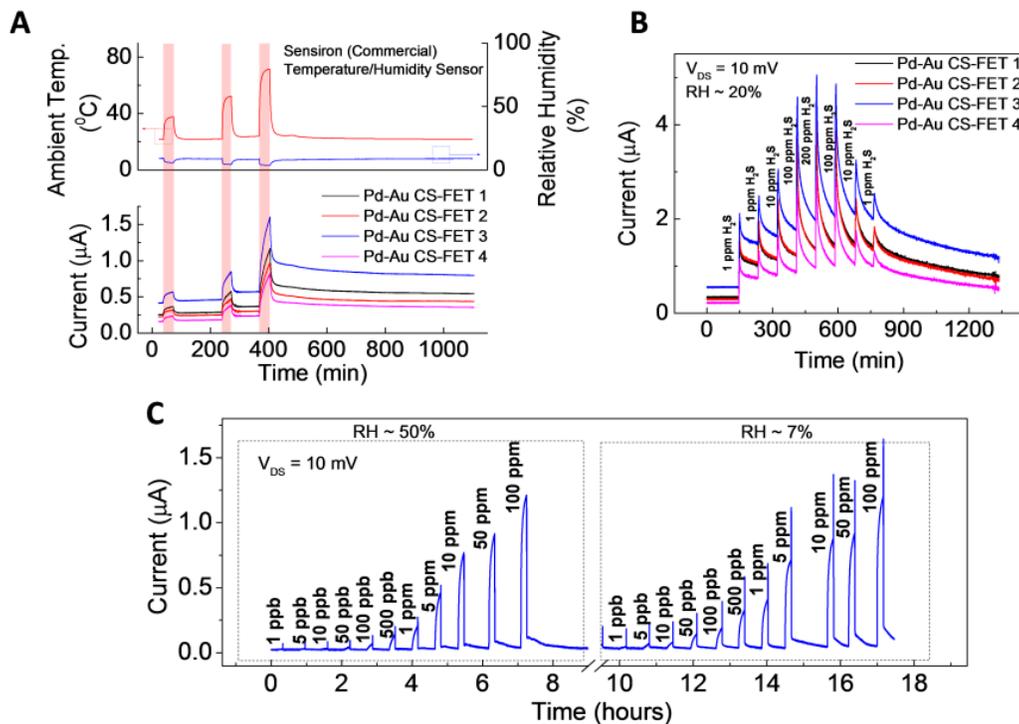


fig. S4. Influence of ambient temperature and humidity on CS-FET sensor response. (A) Effect of ambient temperature on Pd-Au based H_2S CS-FET characteristics ($V_{\text{DS}} = 10 \text{ mV}$, $V_{\text{BG}} = 0 \text{ V}$, $\text{RH} \sim 20\%$, $T \sim 25^{\circ}\text{C}$), **(B)** un-assisted, room temperature recovery from H_2S in Pd-Au CS-FET and **(C)** influence of humidity on a Pd-Au based H_2S sensitive CS-FET.

S5. Individual sensor cycling from low and high gas concentrations

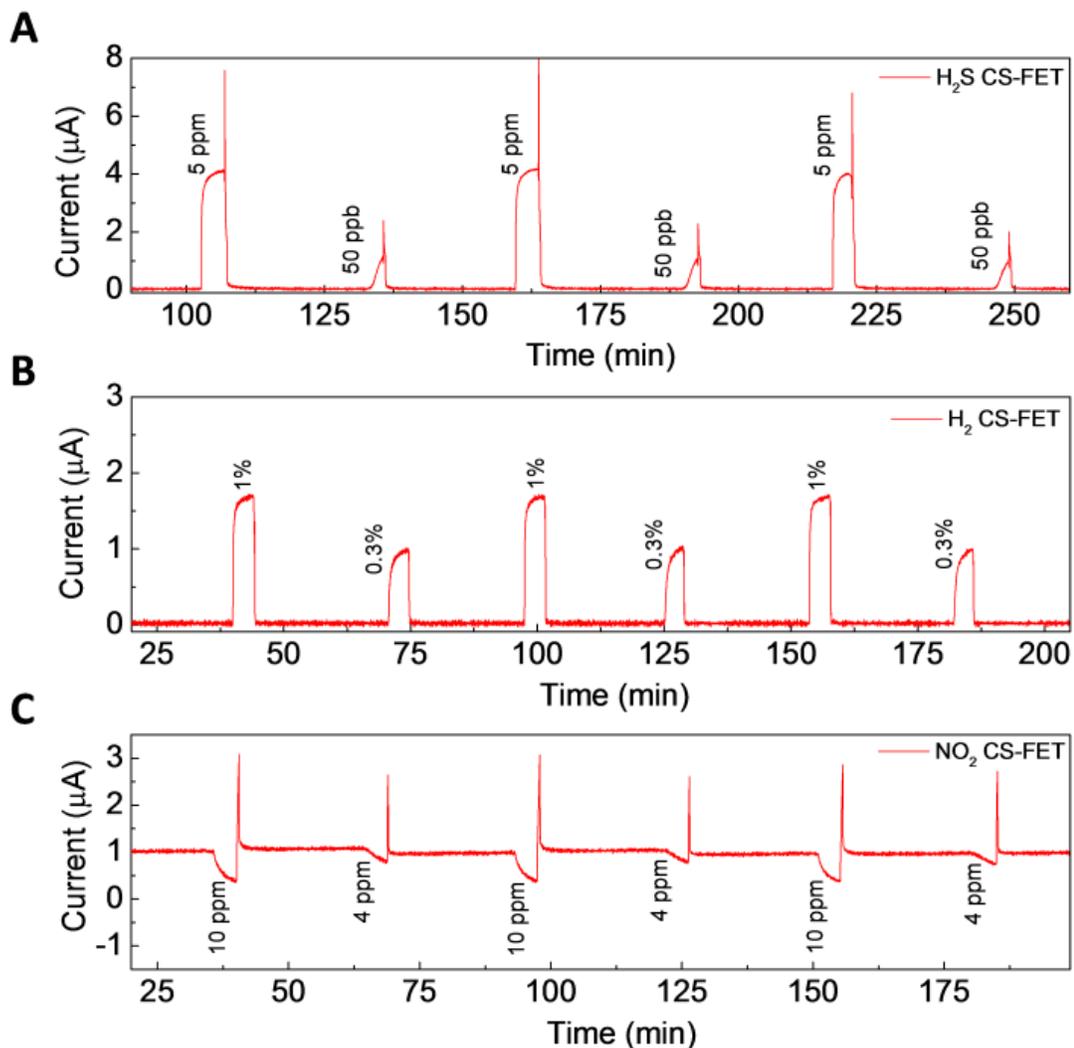


fig. S5. High-low-high gas concentration cycling of CS-FET sensors. (A) Pd-Au based H_2S CS-FET ($V_{\text{DS}} = 1 \text{ V}$, $V_{\text{BG}} = 0 \text{ V}$, RH $\sim 25\text{-}35\%$, $T \sim 25^\circ\text{C}$), (B) Ni-Pd based H_2 CS-FET ($V_{\text{DS}} = 100 \text{ mV}$, $V_{\text{BG}} = 0 \text{ V}$, RH $\sim 25\text{-}35\%$, $T \sim 25^\circ\text{C}$) and (C) Ni based NO_2 CS-FET ($V_{\text{DS}} = 1 \text{ V}$, $V_{\text{BG}} = 10 \text{ V}$, RH $\sim 25\text{-}35\%$, $T \sim 25^\circ\text{C}$). [Experiments were carried out using CS-FET sensors made using SOI wafers procured from Shin-Etsu, Japan – see Materials and Methods section for more details].

S6. Fabrication process of chemical-sensitive 3.5-nm-thin silicon transistors

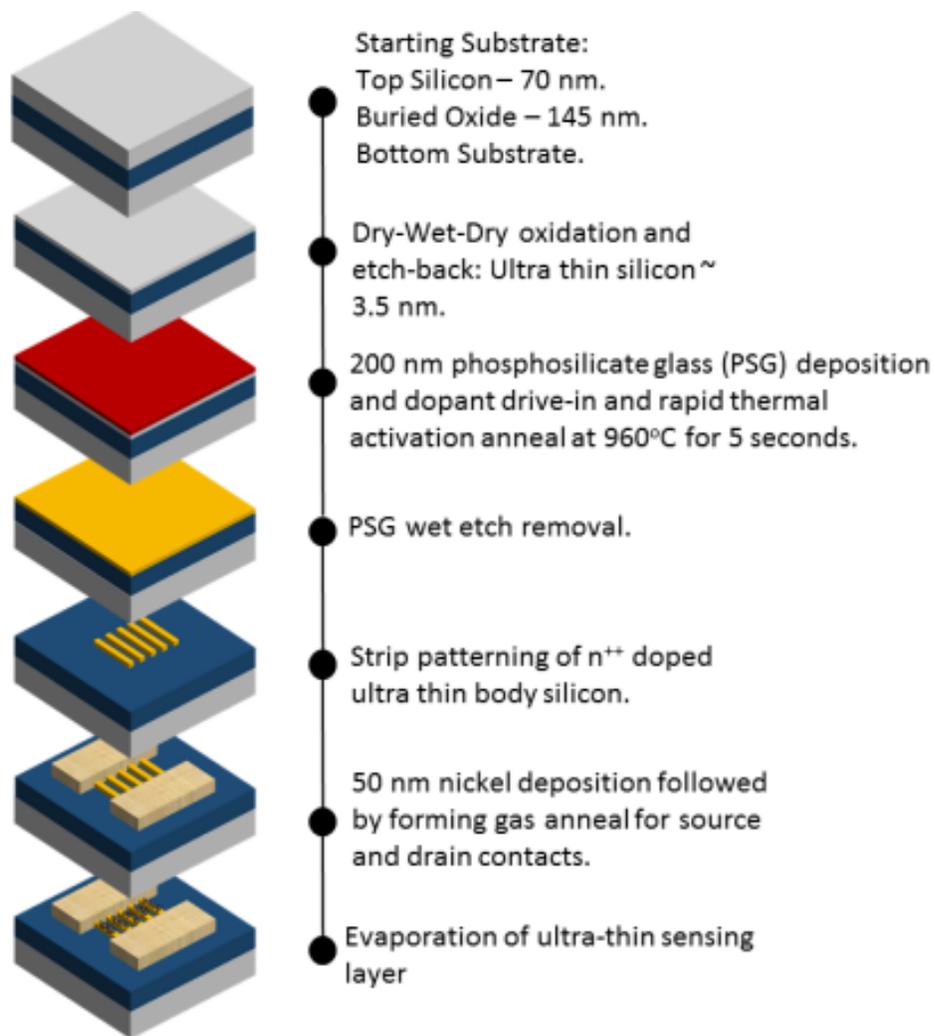


fig. S6. CMOS-compatible fabrication process of CS-FETs.

S7. Microheater characterization

In order to identify a reasonable choice of μ -Heater materials, we investigated a few well known low resistance thin-film materials with the capability to offer sufficient heating without breakdown. From the I-V characteristics in supplementary fig. S7, Au/Cr and Cu are the best in terms of low resistance materials offering higher temperature heating at relatively lower voltage and hence power. Cu as a thin-film heater material was not used on account of its instability at higher temperatures with a tendency to breakdown (burn-out) after repeated heating cycles. Furthermore, Cu tends to be highly reactive with sulfur containing gases making it unsuitable for recovery from corrosive gases like H₂S. Based on this, Au/Cr was used as the μ -Heater material. Supplementary fig. S7B depicts the optical characterization of a single Au (200 nm)/Cr (20 nm) in the dual μ -Heater arrangement using infra-red (IR) microscopy. In order to correlate this with the approximate local surface temperature, one of the μ -Heaters in the dual μ -Heater configuration was used as a temperature sensor. This way the surface temperature around the CS-FET due to heat radiated by a single μ -heater could be approximated and correlated with the IR data. Supplementary fig. S7C shows the calibrated Au (200 nm)/Cr (20 nm) temperature sensor reading due to heat radiated from the adjacent μ -Heater (inset shows the linearity of the temperature sensor). In the final configuration of the CS-FET chip, thicker Au (400 nm)/Cr (20 nm) was used as the heater material to achieve a relatively lower operative voltage affording higher heating temperatures for sensor recovery. In all time-dependent sensor measurements, a recovery temperature ~ 200 °C was used for 5-30 seconds corresponding to ~ 100 mA from a single μ -heater made of Au (400 nm) / Cr (20 nm). Better choice of μ -Heater materials, pattern design and placement can be made to minimize heat loss, thereby lowering μ -heater power consumption.

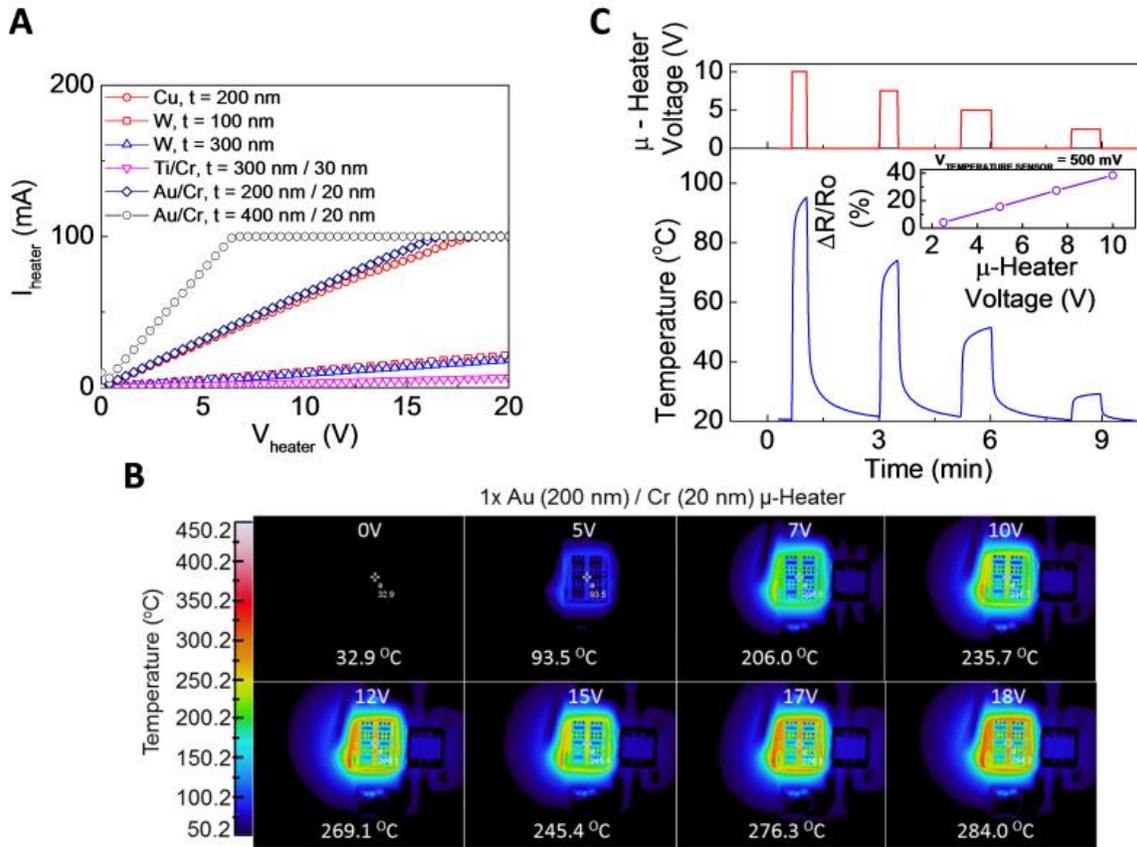


fig. S7. Integrated microheater material selection and characterization. (A) I-V characteristics of micro-heater (μ -Heater) with different materials and thicknesses, (B) infra-red (IR) characterization of a single Au (200 nm) / Cr (20 nm) μ -Heater and (C) Local surface temperature characterization due to radiated heat from a single Au (200 nm) / Cr (20 nm) μ -Heater around the vicinity of the CS-FET, using the adjacent μ -Heater (from the dual heater arrangement) as a single temperature sensor (Inset: Linearity of the temperature sensor; sensitivity vs dissipated heat from adjacent μ -Heater).

S8. Transfer characteristics of H₂S, H₂, and NO₂ CS-FETs

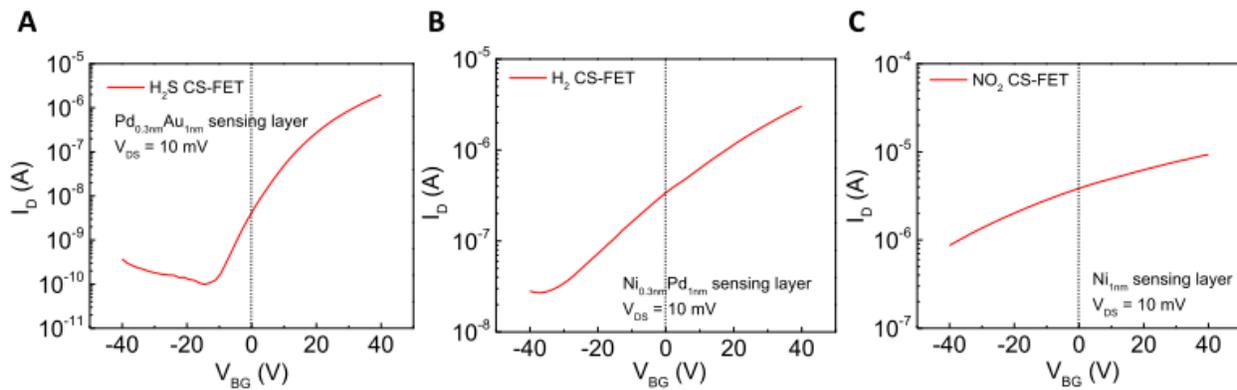


fig. S8. Typical electrical transfer characteristics (I_D - V_{BG}) of functionalized CS-FETs. (A) Pd-Au CS-FET for H₂S detection, (B) Ni-Pd CS-FET for H₂ detection and (C) Ni CS-FET for NO₂ detection.